

PATENT ABSTRACTS OF JAPAN

(11)Publication number : 06-188169

(43)Date of publication of application : 08.07.1994

(51)Int.Cl.

H01L 21/027

G02B 27/28

G03F 7/20

G11B 5/127

G11B 5/31

(21)Application number : 05-212198

(71)Applicant : CANON INC

(22)Date of filing : 04.08.1993

(72)Inventor : UNNO YASUYUKI

(30)Priority

Priority number : 04247249 Priority date : 24.08.1992 Priority country : JP

(54) METHOD OF IMAGE FORMATION, EXPOSURE SYSTEM, AND MANUFACTURE OF DEVICE

(57)Abstract:

PURPOSE: To provide an image formation and an exposure system, in which a repetitive pattern is projected using most properly polarized light to obtain a high-resolution image.

CONSTITUTION: A repetitive pattern on a reticle 4 is illuminated by a lighting system. A beam of light diffracted from the pattern is admitted to the pupil of an optical projection system to project the pattern onto a wafer 6. A deflector 9 is used to select a projection beam that is linearly polarized in a plane perpendicular substantially to the direction in which the period of the pattern is minimized.

